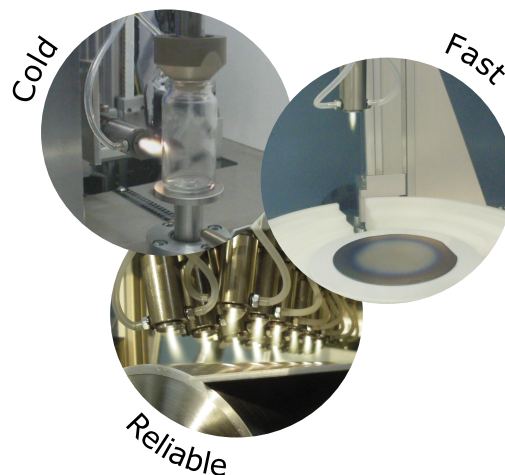
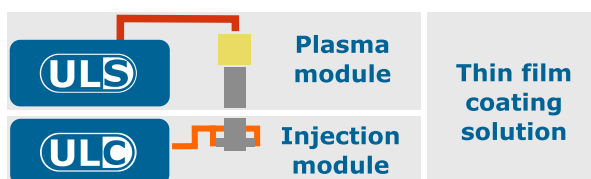


Atmospheric plasma thin film silicon oxide coating

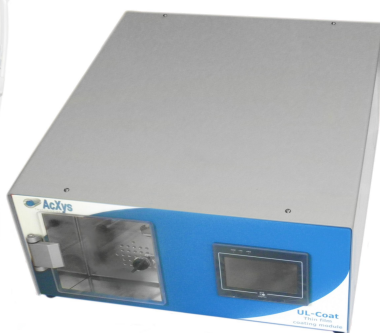
- Thin film coating of SiO_2 or SiO_x
- Operating in open air
- Cold and fast coating
- Easy to use
- Easy to carry & integrate



ULS nozzle
(not included)



Injection
nozzle



precursor injection
device

Precursor injection module

- HMDS type liquid precursor
- Liquid precursor and carrier gas flows control
- Touch screen interface
- Injection nozzle compatible with ULS nozzle
- Stand-alone or OEM

Industrial applications

Gas barrier layer



Deposited into a plastic container or glass, SiO_2 provides tightness between the atmosphere and content.

anti-corrosive layer



The properties of SiO_2 can be used to limit interaction between solids and liquids, or migration of certain elements in metals.

Anti-scratch layer



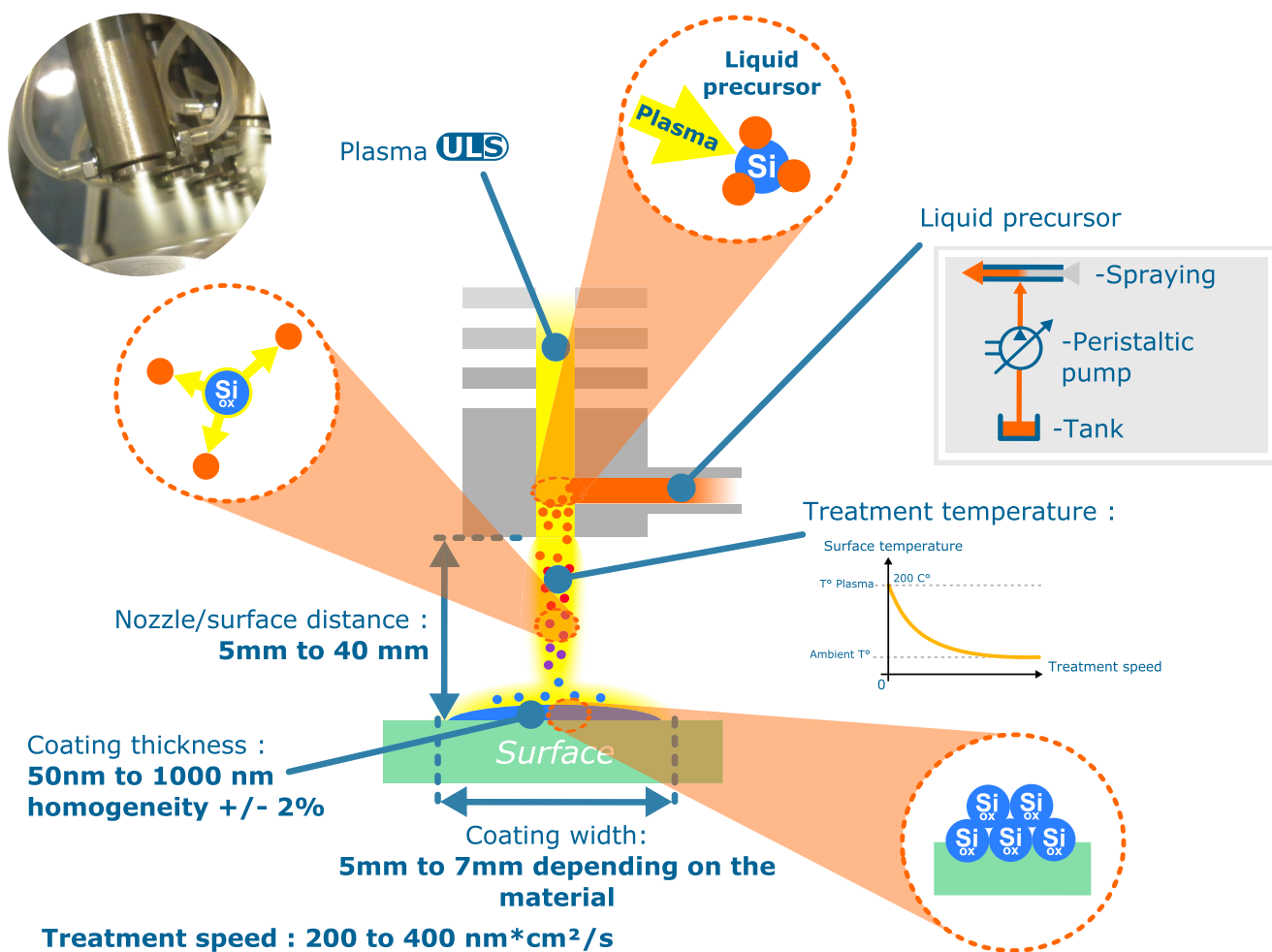
The thickness and strength of SiO_2 provide an anti-scratch property on sensitive materials.

Other...



Acxys Technologies also offers the opportunity to develop new deposits for new applications: TiO_2 , Cu, SnO_2 ...

SiO₂ coating using atmospheric plasma



Technical details

Precursor injection module	Module size	Length:520 mm Width:460 mm Height:210mm
	Module weight	15 Kg
	Power supply	230V - 50/60Hz - 2A
	Carrier gas	Compressed air or nitrogen
	Extraction flow recommended	10 m3/h
	Liquid precursor	HDMS, n° CAS 1450-14-2
	Precursor tank	30ml
SiO₂ coating	Thickness	50nm to 1000nm
	Homogeneity	+/- 2%
	Roughness	Ra <2nm (for 50nm thickness)
	Transmittance	>98% for 50nm thickness